

### **Corporate Profile**

The pioneer of GaO<sup>TM</sup> power device with world-record performance SEMI ecology<sup>TM</sup>

April 2, 2021 FLOSFIA Inc.



### **Trade Name**

### FLOSFIA INC.

### **Head Office**

1-29 Goryo-Ohara, Nishikyo-ku, Kyoto

Business

- (1) Development and manufacture of next-generation semiconductor materials "gallium oxide" (GaO™) devices
- (2) Development and manufacture of new electronic materials and industrial materials produced by MIST DRY<sup>TM</sup> method

**Establishment** 

March 31, 2011

Capital

4,208 million yen (including capital reverse)

Саріта

President: Toshimi Hitora [CEO]

Director: Fujio Okui [COO]

Director: Takashi Shinohe [CTO]
Director: Chinami Majima [CFO]

Management Officers

Outside Director: Yasuo Nishiguchi (Part-Time)
Outside Director: Naonori Kurokawa (Part-Time)
Outside Director: Satoshi Yamaguchi (Part-Time)

Full-Time Auditor: Kazuyuki Nishida

Outside Auditor: Hideki Tsuji (part-time)
Outside Auditor: Tatsuo Mori (part-time)



Toshimi Hitora
President and CEO



Fujio Okui COO



Shareholders (excluding individual

investors)

Brother Industries, Yaskawa Electric, Mitsubishi Heavy Industries, DENSO, SPARX Asset Management (Mirai Creation Fund), JSR, SBI investment (Mitsui Kinzoku-SBI Material Innovation Fund), Fujimi Inc.

University of Tokyo Edge Capital, Nissay Capital, Miyako Capital, Energy Environmental Investment, Eight Roads Ventures, Kyoto University Innovation Capital, etc.

Number of Employees

[57]



### Japan Venture Award 2019, Semiconductor of the Year 2020, and more

▼ November, 2011 IBTEC (Intel & UC Berkeley)
First Finalist as Japanese company





▼ March, 2017 JEITA [ 2<sup>nd</sup> Venture Award] Prize-winning





▼ April, 2017 MUFG 「Rise Up Festa」 Prize-winning





▼ August, 2017 [University venture award] Prize-winning



▼ April, 2019 [Intellectual property Award]



▼ June, 2020 Electric Device Industry News [Semiconductor of the Year] Grand prixs-winning ▼ June, 2018 METI [J-StartUp]
Nomination



▼ January, 2019 [Japan Venture Awards 2019] METI Prize-winning







# FLOSFIA Commercialized Innovative "Gallium Oxide Power Device" Fastest in the World

- 1. Power Device Market Expansion
- 2. GaO™ Power Device Key Advantages
- 3. GaO™ Power Device Business Model
- 4. GaO™ Power Device Growth Strategy
- 5. Film-Deposition Synthesis Technology Platform



### 1. Power Device Market Expansion



# Power Device is a Key Solution to Connect Digital Technology and Environmental Management

### What is a Power Device?

- Key solution to manage electricity in "Smarter Way" at Industry 5.0 / CASE / IoT
- Cover wide-range voltages from Ultra High to Ultra Low across various industries

# Power-Flow Generation Distribution Consumption Power Conversion by Power Device

### **Everywhere & Every Application Transportation Power Grid Electric** Vehicle Factory Solar **Power Device** Automation White **Data Center** Goods

Consumer Product

Power Device in

### 1. Power Device Market Expansion



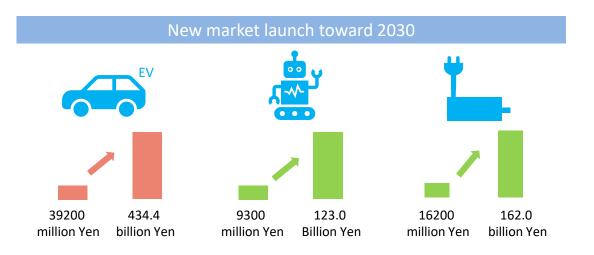
# Power Devices Satisfying Three Requirements are Expected: High Functionality, Energy Saving, and Low Cost

### **Environmental management is a key issue for the SDGs**

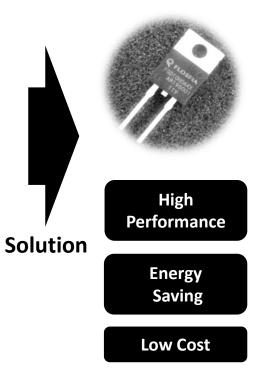
More than 10% of total power generation is lost when conversion. Needs for improved conversion efficiency and increased loss suppression.

### CASE and IoT-based packaging for higher functionality and lower costs

Demand for low-loss and compact of power supplies and inverters increases. Need for sufficient supply of high-performance and low-cost power devices to support the rapid growth of the market



**SEMI** ecology <sup>TM</sup>



Source: Our estimates for the electric vehicle market,

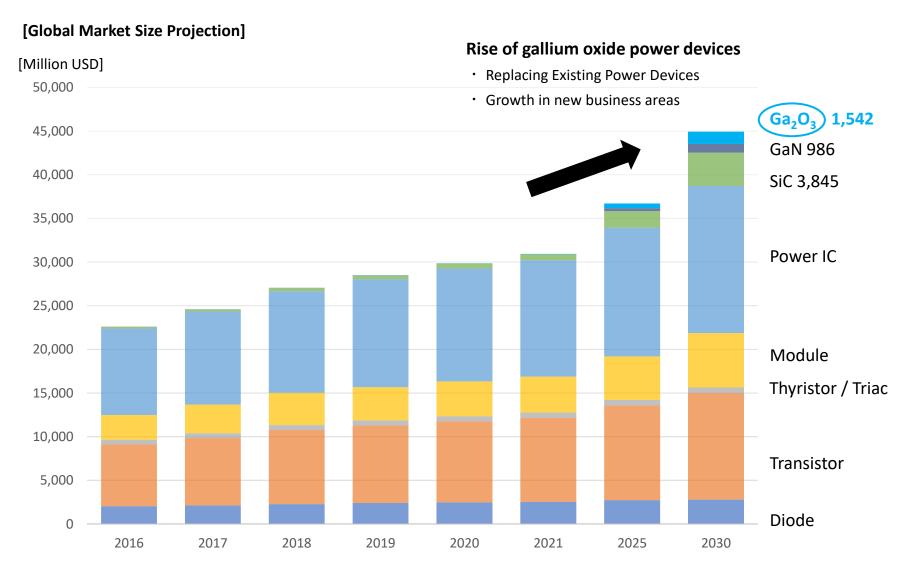
Our estimates for the industrial, consumer, and information and communications equipment areas are based on Fuji Economy's "Current Status and Future of the market for the Next-Generation Power Device and Power Electric-Related Equipment Market" in 2018 edition.

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### 1. Power Device Market Expansion



### Growing Power Device Markets and Growing Expectations for GaO™ Power Devices



### 2. GaO<sup>™</sup> Power Device Key Advantages



# Achieve Ultra-Low Loss and Low Cost with Original Approach Using Corundum-Type Gallium Oxide

|                                      | Existing material Si                               |       | SiC   | State-of-the-arts material α-Ga <sub>2</sub> O <sub>3</sub>   |   |  |
|--------------------------------------|--|-------|---|---|---|--|
| Material                             |  |       | 38  |   | FLOSFIA                                   |  |
| Loss                                 | High loss  |       | Low-loss  | Ultralow loss   |   |  |
|                                      | Bandgap  | 1.1eV | 3.3eV   | 5.3eV   | Advantages of Material Properties         |  |
|                                      | Baluga figure<br>of merit<br>(εμΕ <sub>c</sub> ³)  | 1     | 340   | 6,726<br>(estimated)  | Higher value<br>Low loss!                 |  |
| Cost                                 | Low cost   |       | High cost   | Low cost  | Low cost Know-how advantage               |  |
|                                      | Si exponential comparison                          | 1     | 10  | 1 or less   | Reducing costs through original approach! |  |
| Technology<br>&<br>Business<br>Stage | Monopolize the market<br>Mature process technology |       | No progress of market introduction due to high cost | Only FLOSFIA can manufacture single crystals - Exclusive protection of GaO <sup>™</sup> - [170+] granted and [550+] pending patents |   |  |



### World's First Mass Production of Gallium Oxide Power Device



New material found by Kyoto University
"a-gallium Ga. O.

" $\alpha$ -gallium Ga<sub>2</sub>O<sub>3</sub> (gallium oxide)"



### **Large Implementation Hurdle but Low Attention**

"No proof data on semiconductor characteristics"

"No device verification data"

"p-type semiconductors are difficult to achieve."

"Thermal conductivity is poor and difficult to use."







# For the first time in the world corundum-type Gallium Oxide Power Device

- Utilize sapphire substrate commoditized in use in LEDs
- Discovery and utilization of new p-type semiconductors for breakthrough

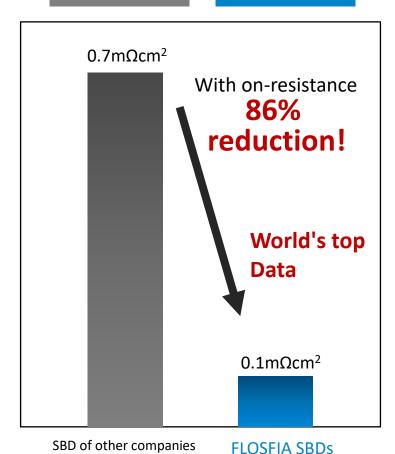


### Achieve "Ultra-Low Loss" at Product Level

### Low - temperature resistance

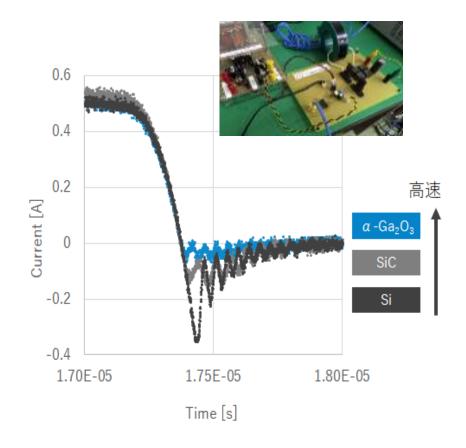
Other materials SiC

GaO<sup>™</sup> device



### High frequency property

### Fast switching confirmed!



3N Resistance[ $m\Omega$ cm $^2$ ]



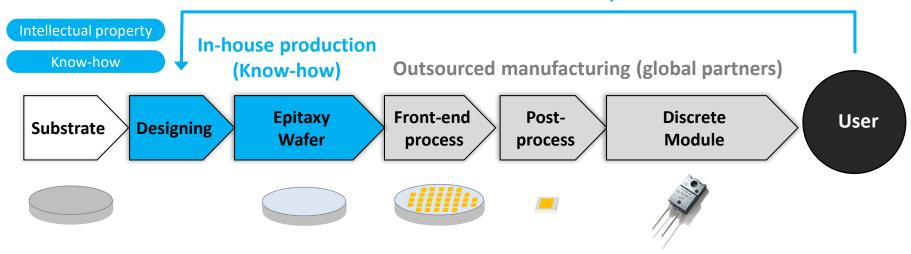
### **Semi-Fabless Model** for Vertical Business Launch with Optimal Investment



### **Key Strength**

- Focus on Core Technology
- Fully utilize external experienced partners
- High Flexibility against market needs and demand fluctuation

### Feedback of user needs to own platform





# Powerful IP Portfolio to Support Unique Business Model and Prevent New Entry

### Focus on acquiring IP(intellectual property)

- Over 550 patent applications
- About 170 patents have already been granted

Point 1

Strong basic patents (material patents) obtained

Point 2

Patents reinforced by a wide range of peripheral patents

Point 3

Worldwide patent portfolio

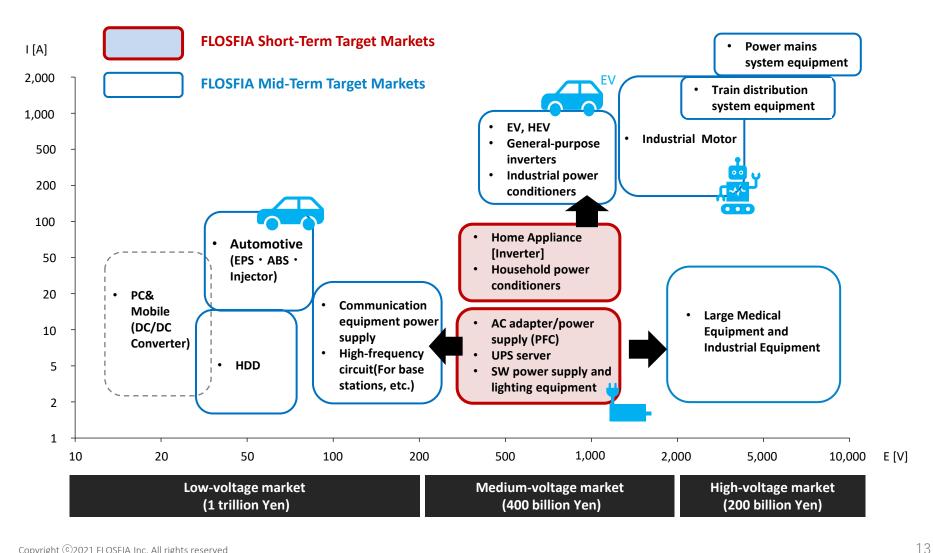


Received the Minister of Economy, Trade and Industry Award as an excellent company actively using intellectual property right system

### 4. GaO<sup>™</sup> Power Device Growth Strategy



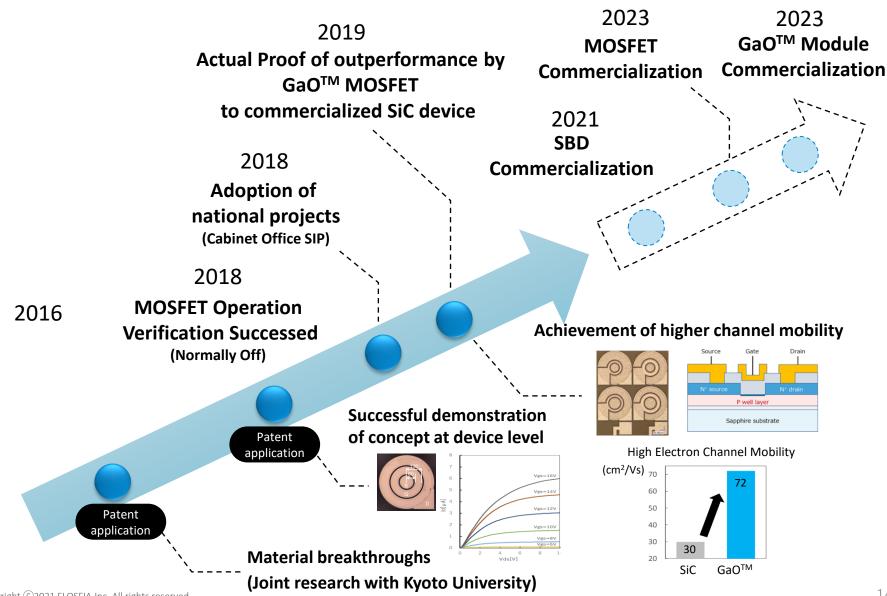
### **Business Expansion** from Medium-Voltage Market to High-Voltage & Low Voltage and Establish World Standard!



### 4. GaO<sup>™</sup> Power Device Growth Strategy



### **Development of Transistor (MOSFET) as Next Pipeline for Steady Progress**

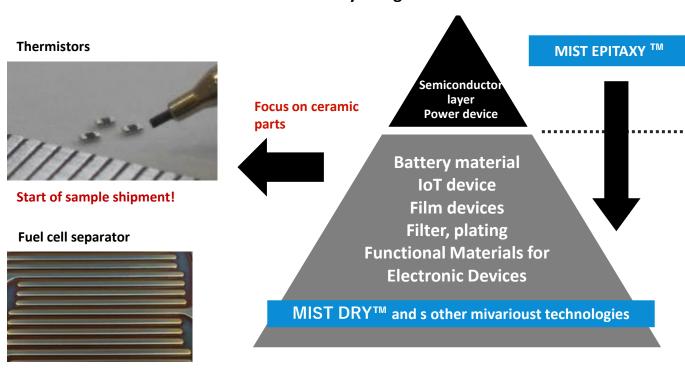


### 5. Film-Deposition Synthesis Technology Platform

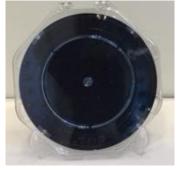


### **Building Unique Platform Utilizing MIST Technologies**

## Platform for Film Deposition Synthesis Technology by using MIST DRY™ method



Film formation on wafers (Larger diameter)



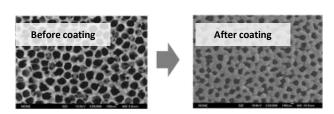
8inche

### Rhodium plating on polyimide



### Gold plating on 4inch wafers





# Utilizing the flow of knowledge and know-how, Contributing to Human Development



Companies gathered flow from various kinds of sophia,

I would like to further refine this sophia and flow it to contribute to the progress of humans.

We have named this type of shape we aim at 'FLOSFIA' ..etc....

Thank you for being utilized in the world and being connected with the world, learn and grow in it, and as a existence that will well satisfy the community and society.

We hope that it will connect again.